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Substitute Specification

Application No. 09/986,303

**PROJECTION EXPOSURE APPARATUS AND
DEVICE MANUFACTURING METHOD USING THE SAME**

FIELD OF THE INVENTION AND RELATED ART

This invention relates to a projection exposure apparatus and a device manufacturing method using the same. More particularly, the invention concerns a projection exposure apparatus and a device manufacturing method which are suitably usable in a projection exposure step in a photolithographic process, specifically, for the manufacture of semiconductor devices such as ICs or LSIs, image pickup devices such as CCDs, display devices such as liquid crystal panels, and magnetic head devices, for example. In the present invention, a continuous emission excimer laser may be used as a light source for transferring a pattern of a reticle onto a photosensitive substrate.

A continuous emission excimer laser can be used as a light source in the manufacture of semiconductor devices or other devices such as liquid crystal panels, for example, based on the photolithographic technology (Japanese Laid-Open Patent Application, Laid-Open No. 163547/1998).